

Replace the Title on page 1, lines 1-2, with the following text:

POST ETCH CLEANING COMPOSITION FOR DUAL DAMASCENE SYSTEM

Amendments to the Claims

Marked up versions of all revised claims, showing insertions and deletions, are included in Appendix B. A clean copy of all claims that will be pending upon entry of this Amendment is attached hereto as Appendix C.

Please rewrite Claim 1 as follows:

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1. (Amended) A composition for removal of etch residues from integrated circuits using cooper materials, which comprises a choline compound, water and an organic solvent.

REMARKS

Applicant has amended the specification to reflect a more concise Title.

Applicant has amended the claims to more particularly recite and distinctly point out what they believe to be the invention.

The above-made amendment does not introduce new matter and Applicant respectfully requests entry of the amendment and remarks made herein in the file of the above-identified application. The pending claims are believed to be in allowable form and Applicant requests that Examiner consider this application with a view toward allowance.

The Examiner is invited to call the undersigned attorney if a telephone call could help Examiner's consideration of such claims.